

IN THE CLAIMS

1. (currently amended) Glass-ceramics having an average linear thermal expansion coefficient within a range of $0.0 \pm 0.2 \times 10^{-7}/^{\circ}\text{C}$ within a temperature range from 0°C to 50°C , having difference between the maximum value and the minimum value of $\Delta L/L$ of 10×10^{-7} or below, and comprising SiO_2 , Al_2O_3 and P_2O_5 with the total amount thereof in mass % being within a range from 86.0% to 89.0% and further comprising CaO in an amount of 0.5 mass % or more, wherein the ratio of P_2O_5 to Al_2O_3 in mass % is within a range from 0.270 to 0.33.

2. (currently amended) Glass-ceramics as defined in claim 1 wherein the ratio of P_2O_5 to SiO_2 in mass % and the ratio of P_2O_5 to Al_2O_3 are

$\text{P}_2\text{O}_5/\text{SiO}_2$ 0.1230 – 0.1450 and

$\text{P}_2\text{O}_5/\text{Al}_2\text{O}_3$ 0.270 – 0.330.

3. (currently amended) Glass-ceramics having an average linear thermal expansion coefficient within a range of $0.0 \pm 0.1 \times 10^{-7}/^{\circ}\text{C}$ within a temperature range from 0°C to 50°C , having difference between the maximum value and the minimum value of $\Delta L/L$ of 8×10^{-7} or below, and comprising SiO_2 , Al_2O_3 and P_2O_5 with the total amount thereof in mass % being within a range from 86.0% to 89.0% and further comprising CaO in an amount of 0.5 mass % or more, wherein the ratio of P_2O_5 to Al_2O_3 in mass % is within a range from 0.270 to 0.33.

4. (currently amended) Glass-ceramics as defined in claim 3 wherein the ratio of P_2O_5 to SiO_2 in mass % and the ratio of P_2O_5 to Al_2O_3 are

$\text{P}_2\text{O}_5/\text{SiO}_2$ 0.1230 – 0.1450 and

$\text{P}_2\text{O}_5/\text{Al}_2\text{O}_3$ 0.270 – 0.330.

5. (original) Glass-ceramics as defined in claim 1 wherein surface roughness (Ra)

(arithmetic mean roughness) is 3 Å or below.

6. (original) Glass-ceramics as defined in claim 1 wherein an average crystal grain diameter of precipitating crystal phase or phases is within a range from 50nm to 90nm.

7. (original) Glass-ceramics as defined in claim 1 which comprise β -quartz (β -SiO₂) and/or β -quartz solid solution (β -SiO₂ solid solution) as a predominant crystal phase.

8. (original) Glass-ceramics as defined in claim 1 which are free of PbO, Na₂O, K₂O and B₂O₃.

9. (original) Glass-ceramics as defined in claim 1 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

| | |
|--------------------------------|----------------|
| SiO ₂ | 53 – 57% |
| P ₂ O ₅ | 7.0 – 8.5% and |
| Al ₂ O ₃ | 23 – 26% |

and is substantially free of PbO, Na₂O, K₂O and B₂O₃, said glass-ceramics comprising β -quartz (β -SiO₂) and/or β -quartz solid solution (β -SiO₂ solid solution) as a predominant crystal phase.

10. (original) Glass-ceramics as defined in claim 9 comprising, in mass %, Li₂O within a range of 3.5 – 4.5%.

11. (original) Glass-ceramics as defined in claim 10 comprising, in mass %,

| | |
|------------------|-------------------|
| MgO | 0.5 – 1.5% and/or |
| ZnO | 0.1 – 1.5% and/or |
| CaO | 0.5 – 1.5% and/or |
| BaO | 0.5 – 1.5% and/or |
| TiO ₂ | 1.5 – 3.0% and/or |
| ZrO ₂ | 1.0 – 3.0% and/or |

As₂O₃ 0.5 – 1.0%.

12. (original) Glass-ceramics as defined in claim 1 wherein the maximum temperature of the heat treatment for crystallization is within a range from 750°C to 800°C.
13. (currently amended) A mask for lithography using comprising glass-ceramics as defined in claim 1.
14. (currently amended) An optical system reflecting mirror for lithography using comprising glass-ceramics as defined in claim 1.
15. (currently amended) A wafer stage or a reticle stage for lithography using comprising glass-ceramics as defined in claim 1.
16. (currently amended) A component part of a precision instrument using comprising glass-ceramics as defined in claim 1.
17. (original) Glass-ceramics as defined in claim 3 wherein surface roughness (Ra) (arithmetic mean roughness) is 3 Å or below.
18. (original) Glass-ceramics as defined in claim 3 wherein an average crystal grain diameter of precipitating crystal phase or phases is within a range from 50nm to 90nm.
19. (original) Glass-ceramics as defined in claim 3 which comprise β-quartz (β-SiO₂) and/or β-quartz solid solution (β-SiO₂ solid solution) as a predominant crystal phase.
20. (original) Glass-ceramics as defined in claim 3 which are free of PbO, Na₂O, K₂O and B₂O₃.
21. (original) Glass-ceramics as defined in claim 3 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

| | |
|--------------------------------|----------------|
| SiO ₂ | 53 – 57% |
| P ₂ O ₅ | 7.0 – 8.5% and |
| Al ₂ O ₃ | 23 – 26% |

and is substantially free of PbO, Na₂O, K₂O and B₂O₃, said glass-ceramics comprising β -quartz (β -SiO₂) and/or β -quartz solid solution (β -SiO₂ solid solution) as a predominant crystal phase.

22. (original) Glass-ceramics as defined in claim 21 comprising, in mass %, Li₂O within a range of 3.5 – 4.5%.

23. (currently amended) Glass-ceramics as defined in claim 22 comprising, in mass %,

| | |
|--------------------------------|------------------------|
| MgO | 0.5 – 1.5% and/or |
| ZnO | 0.1 – 1.5% and/or |
| CaO | 0.5 – [1/] 1.5% and/or |
| BaO | 0.5 – 1.5% and/or |
| TiO ₂ | 1.5 – 3.0% and/or |
| ZrO ₂ | 1.0 – 3.0% and/or |
| As ₂ O ₃ | 0.5 – 1.0%. |

24. (original) Glass-ceramics as defined in claim 3 wherein the maximum temperature of the heat treatment for crystallization is within a range from 750°C to 800°C.

25. (currently amended) A mask for lithography using comprising glass-ceramics as defined in claim 3.

26. (currently amended) An optical system reflecting mirror for lithography using comprising glass-ceramics as defined in claim 3.

27. (currently amended) A wafer stage or a reticle stage for lithography using comprising glass-ceramics as defined in claim 3.

28. (currently amended) A component part of a precision instrument ~~using~~ comprising glass-ceramics as defined in claim 3.

29. (original) Glass-ceramics as defined in claim 2 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

| | |
|--------------------------------|----------------|
| SiO ₂ | 53 – 57% |
| P ₂ O ₅ | 7.0 – 8.5% and |
| Al ₂ O ₃ | 23 – 26% |

and is substantially free of PbO, Na₂O, K₂O and B₂O₃, said glass-ceramics comprising β -quartz (β -SiO₂) and/or β -quartz solid solution (β -SiO₂ solid solution) as a predominant crystal phase.

30. (original) Glass-ceramics as defined in claim 29 comprising, in mass %, Li₂O within a range of 3.5 – 4.5%.

31. (original) Glass-ceramics as defined in claim 30 comprising, in mass %,

| | |
|--------------------------------|-------------------|
| MgO | 0.5 – 1.5% and/or |
| ZnO | 0.1 – 1.5% and/or |
| CaO | 0.5 – 1.5% and/or |
| BaO | 0.5 – 1.5% and/or |
| TiO ₂ | 1.5 – 3.0% and/or |
| ZrO ₂ | 1.0 – 3.0% and/or |
| As ₂ O ₃ | 0.5 – 1.0%. |

32. (original) Glass-ceramics as defined in claim 4 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

| | |
|--------------------------------|----------------|
| SiO ₂ | 53 – 57% |
| P ₂ O ₅ | 7.0 – 8.5% and |
| Al ₂ O ₃ | 23 – 26% |

and is substantially free of PbO, Na₂O, K₂O and B₂O₃, said glass-ceramics comprising β -